

Patent

Attorney's Docket No. 015290-440

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)

Rajinder Dhindsa et al.)

Group Art Unit: 2813)

Application No.: 09/689,845)

Examiner: K. Christianson)

Filed: October 13, 2000)

For: STEPPED UPPER ELECTRODE
FOR PLASMA PROCESSING
UNIFORMITY)I hereby certify that this correspondence is being sent
by Facsimile Transmission to the Assistant
Commissioner For Patents, Washington, D.C. 20231
on:

Date: 1/17/02

Name: Laura Blair

SUPPLEMENTAL AMENDMENT
(Printed name of person signing the
certificate)Assistant Commissioner for Patents
Washington, D.C. 20231

Sign: Laura Blair

(Signature of person signing the certificate)

Sir:

Date: 1/17/02

(Date of Signature)

Further to the Amendment filed December 18, 2001, please amend the application
as follows.

FAX COPY RECEIVED

JAN 17 2002

IN THE CLAIMS:

TECHNOLOGY CENTER 2800

Please cancel Claims 13 and 20 without prejudice or disclaimer of the subject matter
thereof and replace Claims 12 and 19 as follows:12. (Amended) A method of treating a semiconductor substrate in a plasma chamber,
said method comprising the steps of:

supporting the semiconductor substrate on a bottom electrode;

supplying process gas to the chamber;

forming a plasma adjacent an exposed surface of an upper electrode; and

processing the semiconductor substrate with the plasma;